

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
3	BRS	L3	212	((Ge or germanium or Ge?sub\$4) near15 (Se or selenium or Se?sub\$4)) or (GeSe or SeGe)) same (resist or photoresist or photoresin or photosensitive or (photo adj (resist or active or sensitive)))	USPAT; US-P GPUB; EPO; JPO; DERWENT; IBM-TDB-	2004/07/21 11:33	
4	BRS	L5	54	3 and ((remov\$4 or etch\$4 or ash\$4 or clean\$4) with (O2 or oxygen or "O?sub. 2" or O?sub\$2 or dry or RIE))	USPAT; US-P GPUB; EPO; JPO; DERWENT; IBM-TDB-	2004/07/21 11:51	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	210	((Ge or germanium or Ge?sub\$4) near15 (Se or selenium or Se?sub\$4)) or (GeSe or SeGe)) same (resist or photoresist or photoresin or photosensitive or (photo adj (resist or active or sensitive)) same (mask\$4 or photomask\$4))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2004/07/2 1 10:31	
2	BRS	L2	23	1 same (Plasma or oxyen or O2 or "O.sub. 2" or O?sub\$2)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2004/07/2 1 10:32	